



1756

#7

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

WILLIAM R. LIVESAY, ET AL.

Docket: EV-1

Serial Number: 10/090,465

Group Art Unit:

Filed: March 4, 2002

Examiner:

RECEIVED
JUL 16 2003
GROUP 1700

For: METHOD AND APPARATUS FOR MODIFICATION OF CHEMICALLY
AMPLIFIED PHOTORESIST BY ELECTRON BEAM EXPOSURE

UPDATED INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The undersigned wishes to update this file by citing the references enumerated on the enclosed PTO 1449. I hereby certify that each item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.

Respectfully submitted,


Richard S. Roberts

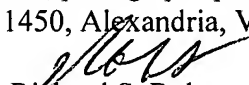
Reg. No. 27,941

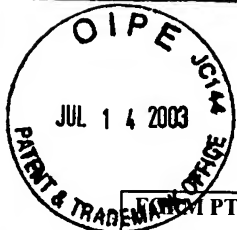
P.O. Box 484

Princeton, New Jersey 08542

Date: July 10, 2003

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage pre-paid in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on July 10, 2003


Richard S. Roberts
Reg.No. 27941



Sheet 1 of 1

PTO-1449 U.S. DEPARTMENT OF
COMMERCE
(Rev. 2-32) PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.:

SERIAL NO.:

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

APPLICANT:

(Use several sheets if necessary)

FILING DATE:

GROUP:

RECEIVED
JUL 16 2003
GROUP 1700

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	2001/0016302 A1	8/23/2001	HIRAYANAGI, ET AL			
	AB	5,003,178	3/26/1991	LIVESAY			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
	AL	WO 96/36070	11/14/1996	PCT				
	AM							
	AN							
	AO							
	AP							

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)

	AQ	Olson, Kurt A., et al "Characterization, modeling and design of an electrostatic chuck with improved wafer temperature uniformity. Rev. Sci. Instrum. 66 (2) February 1995.
	AR	Electrostatic Wafer Holder for Wafer Cooling During Reactive Ion Etching. IBM Technical Disclosure Bulletin Vol. 31, No. 1, June 1988 Armonk, New York
	AS	

EXAMINER

DATE CONSIDERED

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.